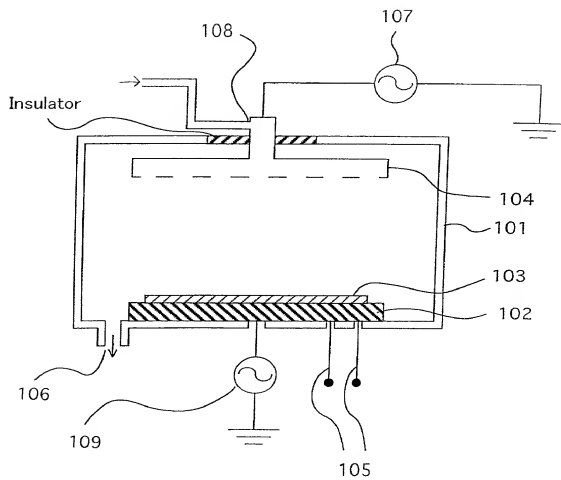
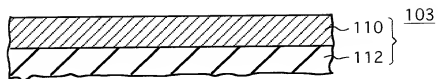


FIG. 1



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FIG. 2A



Processing with Plasma



FIG. 2B

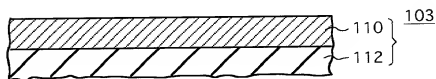


FIG. 2C

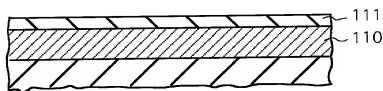
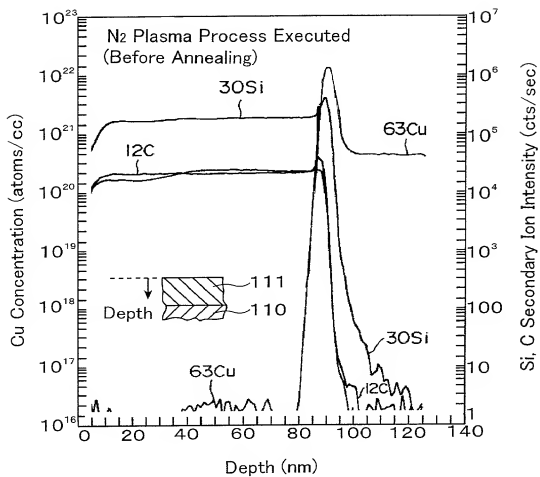


FIG. 3



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FIG. 4

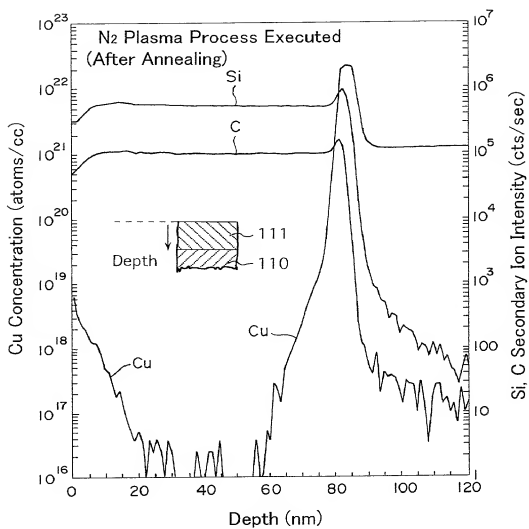
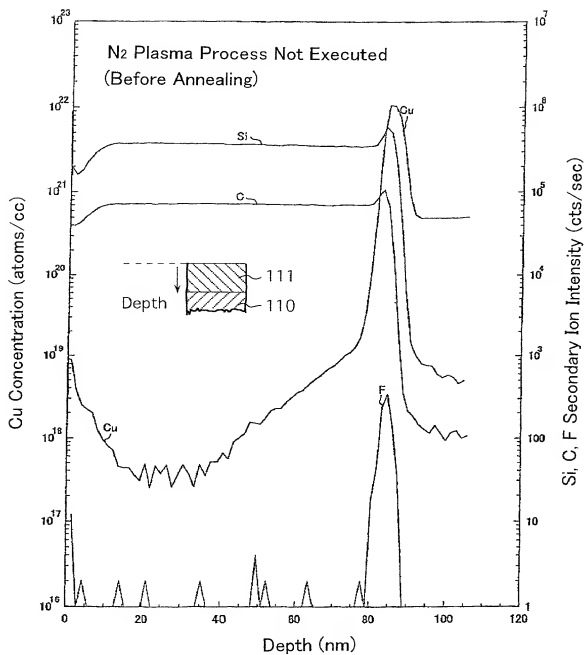


FIG. 5



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FIG. 6

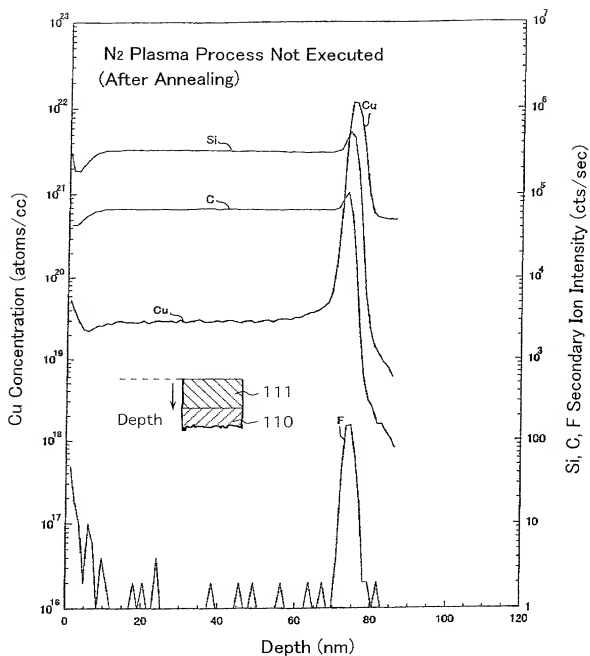


FIG. 7A



FIG. 7B

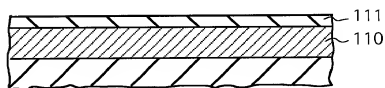


FIG. 7C

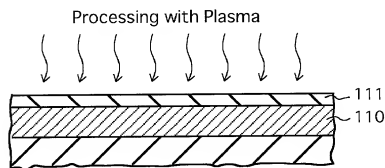


FIG. 8

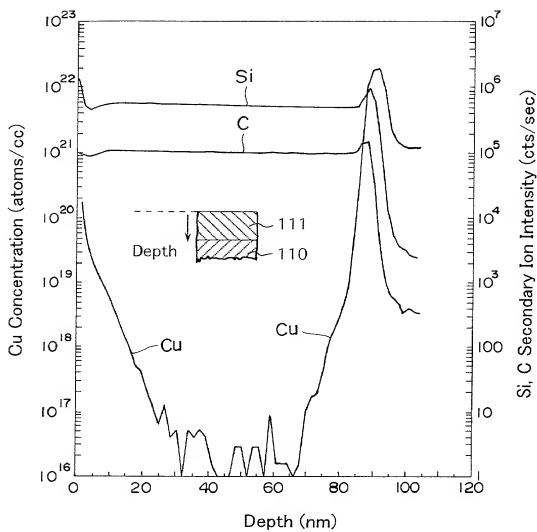




FIG. 9

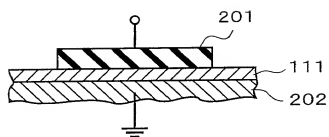


FIG. 10

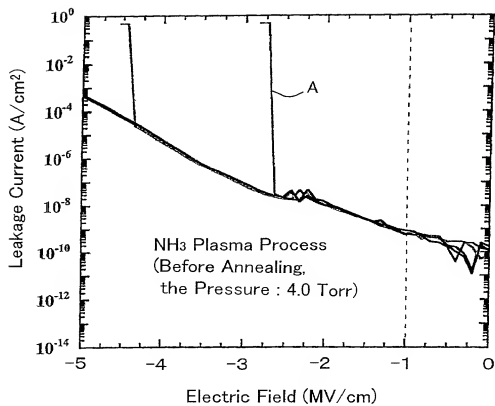


FIG. 11

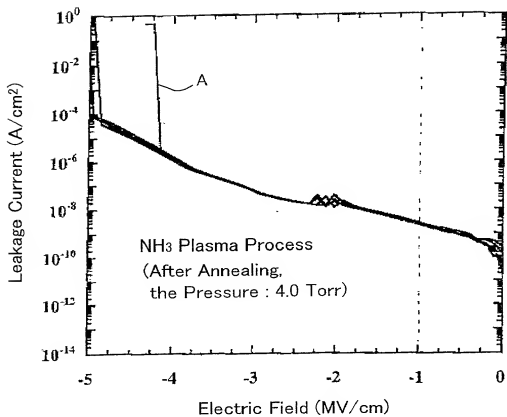


FIG. 12A



FIG. 12B

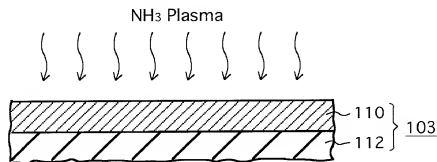


FIG. 12C

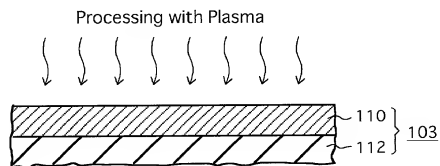


FIG. 12D

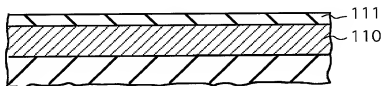


FIG. 12E

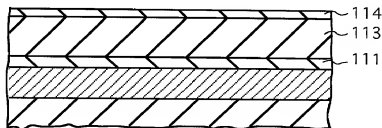


FIG. 12F

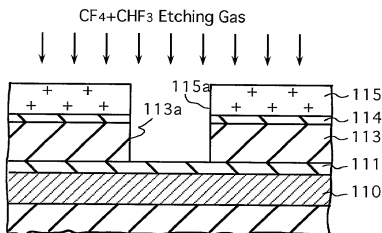


FIG. 12G

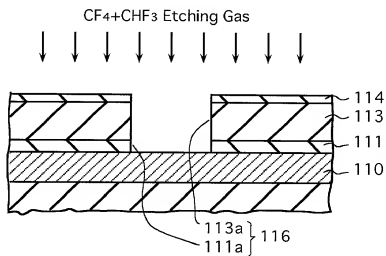
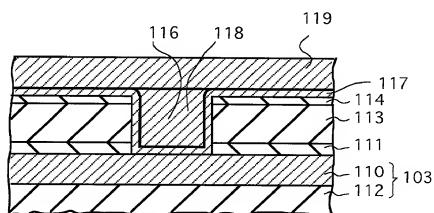


FIG. 12H



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